

ABSTRACT

Exposure method and system for efficiently controlling a non-rotary symmetric component out of imaging characteristics when the light quantity distribution of an exposure beam passing through at least some optical member among a mask and a projection optical system is non-rotary symmetric. A projections exposure system for lighting a reticle (11) with an exposure light (IL) and projecting the pattern of the reticle (11) onto a wafer (18) via a projection optical system (14), wherein a lens (32) in the projection optical system (14) is locally illuminated with correcting lights (LBA, LBB), unlike the exposure light (IL), in a wavelength region easily absorbed by the lens (32) via $1/4$ wavelength plates (51A, 51B) and waveguides (44A, 44B) to thereby control a non-rotary symmetric aberration.